

IN THE CLAIMS:

Please amend claims 1, 5, and 7 as follows:

LISTING OF CURRENT CLAIMS

Claim 1. (Currently Amended) A damper for protecting a sensor of a gauge measuring the pressure of a dry etch chamber, comprising:

a vacuum tube for connecting ~~a~~the gauge with ~~a~~the chamber;

5 at least one plate for blocking ~~a~~the plasma of the chamber from directly striking against ~~a~~the sensor, disposed substantially vertically at anthe inner wall of the vacuum tube; and

at least one wire netting structure located on a front end of the vacuum tube near ~~the chamber. chamber.~~

10 wherein the plasma particles flowing from the chamber through the vacuum tube are firstly deposited and attached onto the plate and will not directly impact the sensor of the gauge.

Claim 2. (Original) The damper of Claim 1, wherein the at least one plate is a stainless steel plate.

Claims 3-4. (Canceled)

Claim 5. (Currently Amended) A damper for protecting a sensor of a gauge measuring the pressure of a dry etch chamber, comprising:

a vacuum tube for connecting ~~a~~the gauge with ~~a~~the chamber; and

5 two plates for blocking ~~a~~the plasma of the chamber from directly striking against ~~a~~the sensor, respectively and separately disposed substantially vertically at anthe upper inner wall and ~~a~~the lower inner wall of the vacuum~~-tube. tube.~~

wherein the plasma particles flowing from the chamber through the vacuum tube are firstly deposited and attached onto the plate and will not directly impact the sensor of the gauge.

Claim 6. (Original) The damper of Claim 5, further comprising a reticular structure disposed at the front end of the vacuum tube near the chamber.

Claim 7. (Currently Amended) A damper for protecting a sensor of a gauge measuring a pressure of a dry etch chamber ~~from plasma particles~~ comprising:

- a) a vacuum tube connecting ~~a~~ the gauge with ~~a~~ the dry etch chamber; and
- 5 b) at least one plate ~~located on an inner wall of the vacuum tube and for~~ blocking the plasma particles of the ~~dry etch~~ chamber from directly striking against ~~the sensor~~. a sensor, disposed substantial vertically at an inner wall of the vacuum tube.

10 wherein the plasma particles flowing from the chamber through the vacuum tube are firstly deposited and attached onto the plate and will not directly impact the sensor of the gauge.

Claim 8. (Original) The damper of Claim 7, wherein the at least one plate is a stainless steel plate.

Claim 9. (Original) The damper of Claim 7, further comprising a reticular structure located on a front end of an interior of the vacuum tube that is connected to the dry etch chamber.

Claim 10. (Original) The damper of Claim 9, wherein the reticular structure is a wire netting.